

**REMARKS**

Claims 1 and 14 have been amended. Claims 11-13 and 16 have been allowed. No claims have been canceled. New claims 17 and 18 have been added. Accordingly, claims 1-18 are currently pending in the application.

**Priority**

Applicants appreciate the Examiner's acknowledgment of the claim for priority and receipt of the foreign priority document.

**35 U.S.C. §§ 102 and 103**

Claims 1-4, 10, 14 and 15 stand rejected under 35 USC 102(b) as being anticipated by Zhang (U.S. Patent No. 5,814,529). Claim 6 stands rejected under 35 U.S.C. §103(a) as being unpatentable over Tanabe et al (U.S. Patent No. 5,998,838). Claims 5 and 7 stand rejected under 35 U.S.C. §103(a) as being unpatentable over Zhang in view of Jung et al (U.S. Patent No. 6,317,173). Finally, claims 8 and 9 stand rejected under 35 USC 103(a) as being unpatentable over Zhang in view of Hara et al (6,046,790). These rejections are traversed as follows.

According to the present invention, the first insulation film has a shape that is different from the second insulation film. Since the second insulation film does not exist around the contact holes, the contact holes can be formed using a single mask. The claims have been amended to emphasize this feature of the present invention.

On the other hand, Zhang uses two masks in order to form contact holes 113 and 114. As described at column 3, lines 47-50, the diameter of the contact holes 113, 114 should be smaller than that of openings 110, 111. Therefore, the diameter of openings 110, 111 should be larger when taking into consideration the registration error of the masks. Thus, the degree of integration of the circuit is reduced.

Furthermore, as suggested from Figs. 4A-4F of Zhang, if patterning were carried out for the first insulation film, the over-ride stairway between the storage electrode 8 and either the source/drain electrode or the pixel electrode would become large. This would create the problem of disconnection.


Therefore, it is preferable that, according to the present invention, the first insulation film is formed to cover the substrate and that the second insulation film is etched so as to be in contact only with an upper surface and side surfaces of the storage electrode and an upper surface of

the first insulation film. As such, it is submitted that the pending claims patentably define the present invention over the cited art.

**Conclusion**

In view of the foregoing amendments and remarks, Applicants contend that the above-identified application is now in condition for allowance. Accordingly, reconsideration and reexamination are respectfully submitted.

Respectfully submitted,

  
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